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Jc872 U.S. PTO
06/09/01



Form PTO-1449

LIST OF PATENTS AND
PUBLICATIONS
FOR INFORMATION
DISCLOSURE STATEMENT
(Use Several Sheets if Necessary)

APPLICANT: Pawitter Mangat et al.

ATTY. DOCKET #: SC11661TP

APPL. #: Unknown

FILING DATE: Concurrently Herewith

GROUP: Unknown

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	ISSUE DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
SR	AA	US 6,261,726 B1	Jul.17,'01	Brooks et al.	430	5	Dec.6,'99
SL	AB	US 6,221,537 B1	Apr.24,'01	Thompson et al.	430	5	Dec.19,'97
SL	AC	6,159,558	Dec.12,'00	Wolfe et al.	427	523	Oct.12,'99
SP	AD	6,140,020	Oct.31,'00	Cummings	430	296	Nov.30,'98
SL	AE	6,124,063	Sep.26,'00	Dauksher et al.	430	5	Jul.30,'98
SL	AF	6,063,246	May 16,'00	Wolfe et al.	204	192.16	May 23,'97
SL	AG	6,051,346	Apr.18,'00	Kornblit et al.	430	5	Jul.23,'98
SL	AH	5,972,794	Oct.26,'99	Katakura	438	704	Mar.18,'98
SL	AI	5,942,760	Aug.24,'99	Thompson et al.	250	492.2	Nov.3,'97
SL	AJ	5,912,095	Jun.15,'99	Katakura	430	5	Jun.3'97
SL	AK	5,899,728	May 4,'99	Mangat et al.	438	459	Dec.22,'97

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	PUBLICATION DATE (#43)	COUNTRY	CLASS	SUBCLASS
	AL					
	AM					
	AN					
	AO					
	AP					

OTHER INFORMATION (Including Author, Title, Date, Pertinent Pages, Etc.)

SR	AR	Donald W. Pettibone et al., "UV Inspection of EUV and SCALPEL Reticles", 20 th Annual BACUS Symp. on Photomask Tech.; Proceedings of SPIE, Vol.4186 (2001);0277-786X/01, pgs.241-249.
SP	AS	Brian J. Grenon et al., "20 th Annual BACUS Symposium on Photomask Technology", 20 th Annual BACUS Symp. on Photomask Tech.; Proceedings of SPIE, Vol.4186 (2001);0277-786X, pgs. 717-723.
SP	AT	H.C.Pfeiffer et al., "Projection reduction exposure with variable axis immersion lenses: Next generation lithography", J. Vac. Sci. Technol. B 17(6), Nov/Dec 1999 American Vacuum Society, pgs. 1-7.
SP	AU	S. Kawata et al., "Stencil reticle development for electron beam projection system", J. Vac. Sci. Technol. B 17(6), Nov/Dec 1999 American Vacuum Society, pgs. 2864-2867.
SP	AV	I.W. Rangelow et al., "p-n junction-based wafer flow process for stencil mask fabrication", J. Vac. Sci. Technol. B 16(6), Nov/Dec 1998 American Vacuum Society, pgs. 3592-3598.
SP	AW	P. Hudek et al., "Directly sputtered stress-compensated carbon protective layer for silicon stencil masks", J. Vac. Sci. Technol. B 17(6), Nov/Dec 1999 American Vacuum Society, pgs. 3127-3131.

EXAMINER

Mohamedulla

DATE CONSIDERED

10/20/03

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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EXAMINER INITIAL		DOCUMENT NUMBER	ISSUE DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
SPM	BA	5,674,413	Oct.7, '97	Pfeiffer et al.	219	121.25	Nov.22, '95
SPM	BB	5,464,711	Nov.7, '95	Mogab et al.	430	5	Aug.1, '94
	BC						
	BD						
	BE						
	BF						
	BG						
	BH						
	BI						
	BJ						
	BK						

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	PUBLICATION DATE (#43)	COUNTRY	CLASS	SUBCLASS
	BL					
	BM					
	BN					
	BO					
	BP					

OTHER INFORMATION (Including Author, Title, Date, Pertinent Pages, Etc.)

	BR	
	BS	
	BT	
	BU	
	BV	
	BW	
	BX	
	BY	
	BZ	

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary)

Sheet _____ of _____

Complete if Known	
Application Number	09/927,024
Filing Date	August 9, 2001
First Named Inventor	Pawitter Mangat
Group Art Unit	1756
Examiner Name	Unassigned
Attorney Docket Number	SC11661TP

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GRANT ID 1700

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OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No. 1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
<i>SPM</i>	CH	PCT/US02/24164 Search Report mailed February 5, 2003.	

Examiner Signature	mohamed ulha	Date Considered	10/20/03
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¹ Unique citation designation number. ² See Kinds of U.S. Patent Documents. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶



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<p>Substitute for form 1449A/PTO</p> <p>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</p> <p>(use as many sheets as necessary)</p>				<p>Complete if Known</p>	
				Application Number	09/927,024
				Filing Date	08-09-2001
				First Named Inventor	Pawitter Mangat
				Group Art Unit	1756
				Examiner Name	Saleha R. Mohamedulla
Sheet	1	of	1	Attorney Docket Number	SC11661TP

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Examiner Signature	Mohamed 2/1/a	Date Considered	10/20/03
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